

# METHOD AND APPARATUS FOR EVALUATION OF MULTILAYER FILM

Publication number: JP2002243669

Publication date: 2002-08-28

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RES INST

Classification:

- international: G01N23/22; G01N23/20; G01N23/22; G01N23/20;  
(IPC1-7): G01N23/22; G01N23/20

- European:

Application number: JP20010038518 20010215

Priority number(s): JP20010038518 20010215

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## Abstract of JP2002243669

**PROBLEM TO BE SOLVED:** To nondestructively evaluate the layer structure and the interface roughness of a multilayer film as a sample, with the multilayer film being irradiated with X-rays. **SOLUTION:** In the method of evaluating the multilayer film, the multilayer film as the sample is irradiated with the X-rays of a prescribed energy (or a prescribed wavelength), the dependence on the incident light energy (or the wavelength) of the amount of a sample current flowing in the multilayer film is measured, an electronic yield X-ray standing-wave spectrum is measured, and the layer structure and the interface roughness are evaluated on the basis of the shape of the spectrum.

